## Stereochemistry of the Reduction of Boron Trichloride by an **Optically Active Silane**

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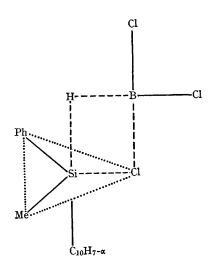
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THE optically active silane, methyl-a-napththylphenylsilane, has already proved to be a powerful tool in the elucidation of a number of reaction mechanisms concerning silicon,<sup>1</sup> but the only reduction studied in this way has been that of triphenylmethyl chloride in a donor solvent.<sup>2</sup>

As part of a systematic study of the reducing properties of silanes, we have now found that methyl-a-naphthylphenylsilane reduces boron trichloride to diborane and is itself converted into the corresponding chlorosilane with at least 90% retention of configuration. Thus, (+)-methyl- $\alpha$ naphthylphenylsilane ( $[\alpha]_{\mathbf{p}}^{20} + 34^{\circ}$ ) reacted with an excess of boron trichloride at room temperature to give diborane (98%), recovered boron trichloride, and (-)-methyl- $\alpha$ -naphthylphenylsilyl chloride (94%) ( $[\alpha]_{D}^{20}$  -5.11°, lit.<sup>1</sup>  $[\alpha]_{D}^{20}$  -6.2°). It is known that the (+)-silane and the (-)-chlorosilane are of the same absolute configuration.<sup>1</sup>

The 90% retention of configuration implies that Si-H bond scission and Si-Cl bond formation are synchronous as required by a four-centred reaction intermediate or transition state (see Figure). A similar four-centred mechanism has been suggested<sup>2,3</sup> for the reaction of triphenylmethyl chloride with silanes.

This result gives support to the tentative suggestion that the gas-phase reactions between methylchlorosilanes,  $Me_nSiHCl_{3-n}$  and boron halides may involve a four-centre mechanism.<sup>4</sup>



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<sup>2</sup> J. D. Austin and C. Eaborn, J. Chem. Soc., 1964, 2279.
<sup>3</sup> J. C. Corey and R. West, J. Amer. Chem. Soc., 1963, 85, 2430.

<sup>4</sup> J. A. Connor, R. N. Haszeldine, and G. J. Leigh, International Symposium on Organosilicon Chemistry, Prague, 1965, Scientific Communications, p. 109.